

RESPONSE UNDER 37 CFR 1.116
EXAMINER'S PROCEDURE
EXAMINING GROUP

PATENT
ATTORNEY DOCKET NO. PHA 23578

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

• Applicant : Fuchs et al. Art Unit: 2877
• Application No.: 09/037,141 Examiner: S. Turner
• Filed: May 28, 1998
• Title: METHOD AND DEVICE FOR MEASURING THIN FILMS AND SEMICONDUCTOR SUBSTRATES

Commissioner of Patents and Trademarks
Washington, DC 20231

AMENDMENT AFTER FINAL REJECTION

In response to the Final Office Action dated April 13, 2000, please amend the above-identified application as follows:

IN THE TITLE:

Please replace the current title with the following

-- METHOD AND DEVICE FOR MEASURING THIN FILMS AND SEMICONDUCTOR SUBSTRATES USING RELECTION MODE GEOMETRY--

IN THE CLAIMS:

Please amend claim 35 as follows:

35. (Twice Amended) An apparatus for measuring a property of a structure, comprising:

a passively Q-switched microchip laser that generates an optical pulse;

a photodiode that receives a portion of the optical pulse to generate a trigger pulse;

a first optical system that receives the optical pulse and separates it into at least two excitation pulses;